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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/811,927	03/30/2004	Junji Noguchi	501.39932CX1	2900
20457	7 7590 03/10/2006		EXAMINER	
ANTONELLI, TERRY, STOUT & KRAUS, LLP 1300 NORTH SEVENTEENTH STREET			AU, BAC H	
SUITE 1800	SEVENTEENTH STR	MILENIH SIRLEI		PAPER NUMBER
ARLINGTON, VA 22209-3873			2822	
			DATE MAILED: 03/10/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

<u>_</u>		Application No.	Applicant(s)		
		10/811,927	NOGUCHI ET AL.		
	Office Action Summary	Examiner	Art Unit		
		Bac H. Au	2822		
Period fo	The MAILING DATE of this communication app or Reply	pears on the cover sheet with the c	orrespondence address		
WHIC - Exte after - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR REPLY CHEVER IS LONGER, FROM THE MAILING D. Insions of time may be available under the provisions of 37 CFR 1.1 SIX (6) MONTHS from the mailing date of this communication. D period for reply is specified above, the maximum statutory period or to reply within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailing ed patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be tin will apply and will expire SIX (6) MONTHS from the cause the application to become ABANDONE	N. nely filed the mailing date of this communication. D (35 U.S.C. § 133).		
Status					
1)⊠	Responsive to communication(s) filed on 30 M	larch 2004.			
2a) <u></u> ☐	☐ This action is <b>FINAL</b> . 2b) ☑ This action is non-final.				
3)	☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is				
	closed in accordance with the practice under E	Ex parte Quayle, 1935 C.D. 11, 4	53 O.G. 213.		
Dispositi	ion of Claims				
5)□ 6)⊠ 7)□	Claim(s) 1-20 is/are pending in the application 4a) Of the above claim(s) is/are withdray Claim(s) is/are allowed. Claim(s) 1-20 is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction and/o	wn from consideration.			
Applicati	ion Papers				
10)⊠	The specification is objected to by the Examine The drawing(s) filed on 30 March 2004 is/are: Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the Ex	a)⊠ accepted or b)⊡ objected to drawing(s) be held in abeyance. Sec tion is required if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 CFR 1.121(d).		
Priority ι	ınder 35 U.S.C. § 119				
a)	Acknowledgment is made of a claim for foreign  All b) Some * c) None of:  1. Certified copies of the priority document  2. Certified copies of the priority document  3. Copies of the certified copies of the priority document  application from the International Bureau  See the attached detailed Office action for a list	s have been received. s have been received in Applicati rity documents have been receive u (PCT Rule 17.2(a)).	on No. <u>09/825,946</u> . ed in this National Stage		
Attachmen		<b></b>	(070,440)		
	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948)	4) Interview Summary Paper No(s)/Mail Da			
3) 🛛 Infor	mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) or No(s)/Mail Date <u>30 March 2004</u> .		atent Application (PTO-152)		

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#### **DETAILED ACTION**

### Claim Objections

1. Claims 1 and 13 are objected to because of the following informalities:

Regarding claim1, "insulting" in line 3 should be --insulating--; "electro plating" in line 17 should be --electroplating--.

Regarding claim 13, "electro plating" in line 17 should be --electroplating--.

Appropriate correction is required.

## **Double Patenting**

The nonstatutory double patenting rejection is based on a judicially created doctrine grounded in public policy (a policy reflected in the statute) so as to prevent the unjustified or improper timewise extension of the "right to exclude" granted by a patent and to prevent possible harassment by multiple assignees. A nonstatutory obviousness-type double patenting rejection is appropriate where the conflicting claims are not identical, but at least one examined application claim is not patentably distinct from the reference claim(s) because the examined application claim is either anticipated by, or would have been obvious over, the reference claim(s). See, e.g., *In re Berg*, 140 F.3d 1428, 46 USPQ2d 1226 (Fed. Cir. 1998); *In re Goodman*, 11 F.3d 1046, 29 USPQ2d 2010 (Fed. Cir. 1993); *In re Longi*, 759 F.2d 887, 225 USPQ 645 (Fed. Cir. 1985); *In re Van Ornum*, 686 F.2d 937, 214 USPQ 761 (CCPA 1982); *In re Vogel*, 422 F.2d 438, 164 USPQ 619 (CCPA 1970); and *In re Thorington*, 418 F.2d 528, 163 USPQ 644 (CCPA 1969).

A timely filed terminal disclaimer in compliance with 37 CFR 1.321(c) or 1.321(d) may be used to overcome an actual or provisional rejection based on a nonstatutory double patenting ground provided the conflicting application or patent either is shown to be commonly owned with this application, or claims an invention made as a result of activities undertaken within the scope of a joint research agreement.

Effective January 1, 1994, a registered attorney or agent of record may sign a terminal disclaimer. A terminal disclaimer signed by the assignee must fully comply with 37 CFR 3.73(b).

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2. Claims 1-20 are rejected on the ground of nonstatutory obviousness-type double patenting as being unpatentable over claims 1-12 of U.S. Patent No. 6764950 in view of Ngo (U.S. Pat. 6348410).

Regarding claims 1-20, Patent '950 discloses most of the limitations of the claims. Patent '950 fails to disclose

- (a) forming a second insulating film over a first major surface of a wafer;
- (b) forming a groove in the second insulating film;
- (c) performing an ammonia plasma treatment to an exposed surface in the groove and hole and a top surface of the second insulating film,
- (d) forming a barrier metal film over inner surfaces of the groove and the hole and over an upper surface of the second insulating film.

However, Ngo [Fig.3] discloses a method wherein

- (a) forming a second insulating film [210] over a first major surface of a wafer;
- (b) forming a groove [204] in the second insulating film;
- (c) performing an ammonia plasma treatment to an exposed surface in the groove and hole and a top surface of the second insulating film [Col.5 lines 46-50; col.4 lines 54-58].
- (d) forming a barrier metal film [232] over inner surfaces of the groove and the hole and over an upper surface of the second insulating film.

It would have been obvious to one of ordinary skill in the art at the time of the invention was made to incorporate the teachings of Ngo into the method of '950 to include

(a) forming a second insulating film over a first major surface of a wafer;

(b) forming a groove in the second insulating film;

(c) performing an ammonia plasma treatment to an exposed surface in the

groove and hole and a top surface of the second insulating film,

(d) forming a barrier metal film over inner surfaces of the groove and the hole

and over an upper surface of the second insulating film.

The ordinary artisan would have been motivated to modify '950 in the manner set forth above for at least the purpose of having multiple metallization layers in the manufacture of integrated circuits, and using the damascene technique to eliminate metal etch and dielectric gap fill steps [Col.3 lines 18-23].

#### Conclusion

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Bac H. Au whose telephone number is 571-272-8795. The examiner can normally be reached on Mon-Fri 8-5.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Zandra Smith can be reached on 571-272-2429. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

BHA

Zandra V. Smith Supervisory Patent Fxaminer

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